

JXA-8530F

Field Emission Electron Probe Microanalyzer

禹重科技[®]UZONGLAB

成分分析仪器|表面测试仪器|样品前处理仪器





A PC Controlled, WD/ED Combined System Opens Doors to New Ultra Micro Analysis

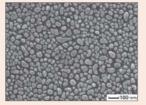
JEOL revolutionized surface analysis with an EPMA featuring a field emission (FE) electron gun, and now is proud to present a new upgraded FE-EPMA.

The JXA-8530F operates on PC Windows for data acquisition and analysis while maintaining the powerful hardware of the JXA-8500F including the FE electron gun, EOS, and vacuum system to achieve the ultra micro area analysis. User friendly, PC-based operation facilitate quick and easy analyses at the highest magnifications.

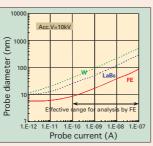


►► High spatial resolution in X-ray mapping with the FE electron gun

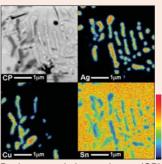
The FE electron gun produces a probe that is only 1/2 to 1/10 the size of that produced in a thermionicemission electron gun in a conventional EPMA, using a W filament or a LaB₆ tip.



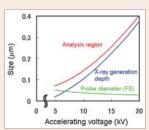
Secondary electron image of gold particles (100,000×)



Probe diameter versus probe current in different guns using 10 kV accelerating voltage.



Backscattered electron image (CP) and X-ray maps of lead free solder (20.000×. 6 kV. 10 nA)



Probe diameter, area of X-ray generation, and analytical area (X-ray spatial resolution) relative to kV in a FE electron gun.

The FE electron gun is capable of producing a micro probe at low accelerating voltage even with high probe currents(10 to 100 nA), allowing for WDS analyses with high X-ray spatial resolution.



"Click Point Analysis", User's Recipes

"Click Point Analysis" allows the user to acquire qualitative WDS spectra and semi-quantitative analyses simply by clicking a point on a secondary electron or backscattered electron image. User's Recipes provides for easy access to preset analytical conditions. These features are designed to maximize the efficiency of the FE-EPMA with the simplest of operations.

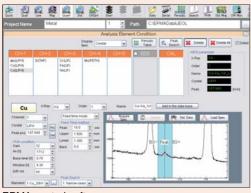


'Click Point Analysis" Selecting Point Analysis will activate WDS qualitative analysis.

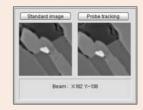


Advanced Operation

A user can design detailed analytical procedures tailored to their research objective, such as complex quantitative elemental analysis of nano-size areas. Also integrated into the system are a complete line of applications and easy-touse software packages that provide for extensive data analysis methods and tools. For example, Probe Tracking is provided making it easier to perform long duration area and spot analyses on extremely small features without concern for beam drift.



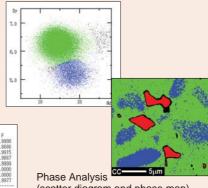
EPMA control software (Settings windows for quantitative analysis conditions)



Probe Tracking

Element	Mass(X)	Atom(X)	K(%)	К-гам(X)	ZAF	Z	Α	F
SI	0.598	1.1747	0.328	0.328	1.8224	0.9007	2.0237	0.999
Cr	19,414	20,6089	22,005	22,005	0.8823	1,0055	1.0102	0.868
Mo	1.713	1.7214	1.684	1,684	1.0175	1.0222	1.0039	0.991
Fe	67,812	67,0238	66,222	66,222	1.0240	1,0016	1.0340	0,988
Co	0.170	0.1590	0.162	0.162	1.0470	1.0202	1.0264	0.999
Ni	9.757	9.1735	8,955	8,955	1.0895	0.9827	1.1087	1,000
Cu	0.070	0.0610	0.083	0.063	1.1161	1.0300	1.0835	1,000
Mo	0.135	0.0778	0.106	0.106			1.1856	0.997

An example of quantitative analysis results

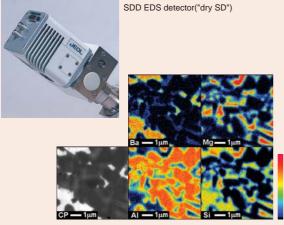


(scatter diagram and phase map)



Combined **WD/ED System**

The JXA-8530F has a user friendly combined WD/ED system incorporating JEOL's advanced WDS and EDS detectors. Combining the WDS for trace element analysis and JEOL's proven EDS, the JXA-8530F is a powerful tool for efficient data acquisition of quantitative analyses, high magnification beam scan mapping, and large area stage scan mapping.



Backscattered electron image (CP) and combined WD/ED x-ray maps (Top: WDS; Bottom: ÉDS)

Specifications

Detectable elements WDS: (Be*) B to U, EDS: B to U

WDS: 0.087 to 9.3 nm. X-ray range

EDS energy range: 20 keV

X-ray spectrometers WDS: 1 to 5; EDS: 1

 $100 \text{ mm} \times 100 \text{ mm} \times 50 \text{ mm} \text{ (H)}$ Maximum sample size

1 to 30 kV (0.1 kV steps) Accelerating voltage

Probe current range 10^{-12} to 5×10^{-7} A

 \pm 0.3 %/h Beam current stability

3 nm (WD 11 mm, 30 kV) SE resolution 40 nm (10 kV, 1×10^{-8} A) Minimum probe size

100 nm (10 kV, 1×10^{-7} A)

Scanning magnification 40 to 300,000× (WD 11 mm) Scanning image resolution Maximum 5120 × 3840

Color display For EPMA analysis: LCD 1280 × 1024

For SEM operation and EDS analysis:

LCD 1280 × 1024

* With optional analyzing crystal for Be analysis

^{*}Specifications and appearance are subject to change without notice due to modification.



Installation requirements

Power supply

Single phase 200 V, 50/60 Hz, 4 kVA Base unit

Allowable input-voltage fluctuation ± 10%

(Ground: One, 100Ω or less)

Computer AC100 V, 50/60 Hz, 15 A or more

Cooling water

Faucet One, JIS B 0203 Rc3/8 (R3/8 on hose end)

Flow rate 3.0 to 3.5 lit/min

Pressure 0.1 to 0.25 MPa (gauge)

Temperature 20 ± 5 °C' Drain 1 or more

> (Drain to accommodate 2 OD 10 mm hoses) *Water chiller (option) recommended

Dry N₂gas To be purchased by user.

Pressure 0.4 to 0.5 MPa (gauge)

Gas outlet JIS B 0203 (ISO7/1) Rc1/4 (female)

PR gas To be purchased by user.

Ar 90 %, CH₄ 10 %

Gas outlet JIS B 0203 (ISO7/1) Rc1/4 (female)

Installation room

Room temperature 20 ± 5 °C (fluctuation : ± 1 °C recommended)

Humidity 60 % or less (no condensation) Stray magnetic field 0.1 μ T(p-p) or less (50/60 Hz)*

0.05 μ T(p-p) or less, vibration of DC magnetic field*

Floor vibration $2 \mu m$ (p-p) or less (at 5Hz)*

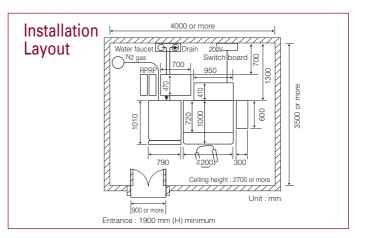
70 dB (F) or less' Acoustic

Floor space 4000 mm (W) × 3500 mm (D)

× 2700 mm (H) minimum

Entrance 900 mm (W) ×1900 mm (H) minimum

* For conditions other than these, we will conduct a room survey prior to installation and determine the highest magnification attainable



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